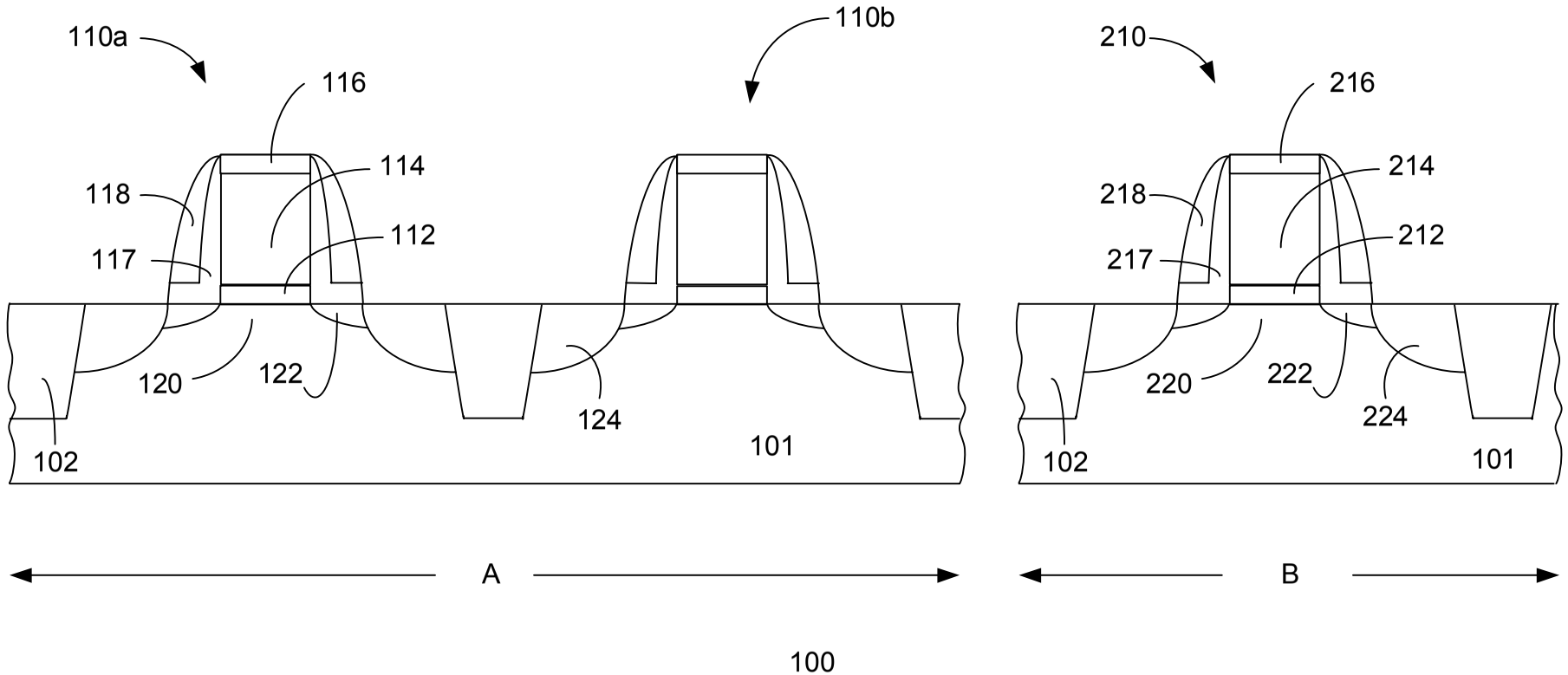
110a
110b
210
116
216
114
214
118
218
112
212
117
217
120
122
124
220
222
224
102
101
102
101
A
B
100

Fig. 1

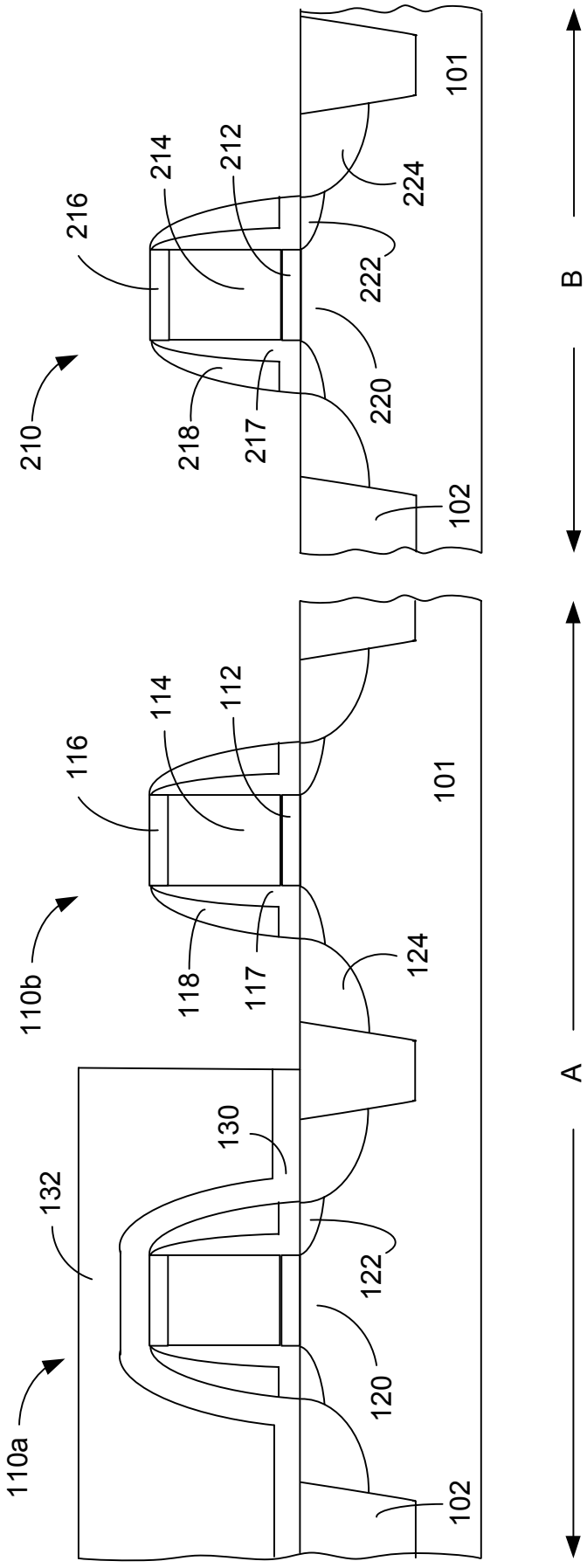
110a
110b
210
132
130
116
114
112
118
117
124
216
214
212
224
222
220
218
217
101
102
120
122
A
B
100

Fig. 2

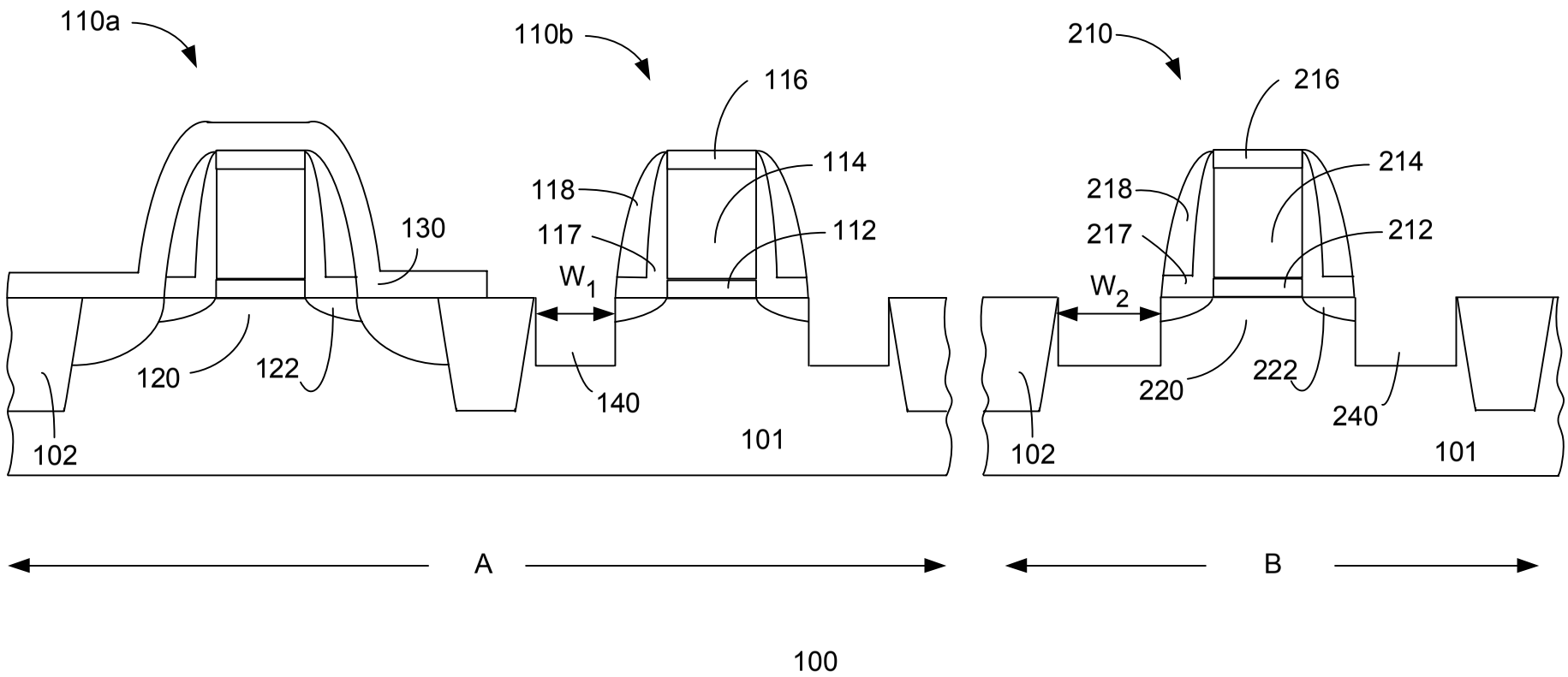
110a
110b
210
116
216
114
214
118
218
117
217
112
212
130
W1
W2
120
122
140
220
222
240
102
101
102
101
A
B
100

Fig. 3

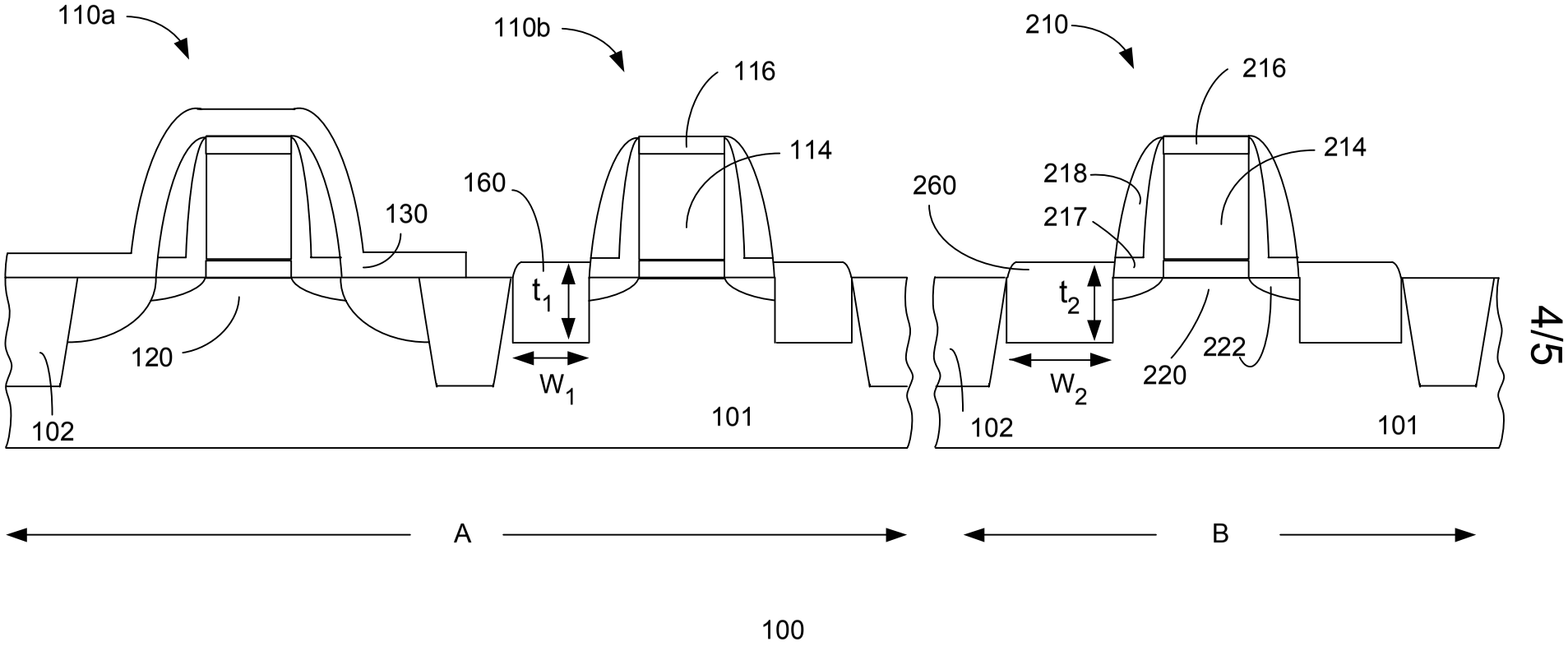
110a
110b
210
116
216
114
214
160
218
260
130
217
t_1
t_2
120
W_1
W_2
220
222
102
101
102
101
A
B
100

Fig. 4

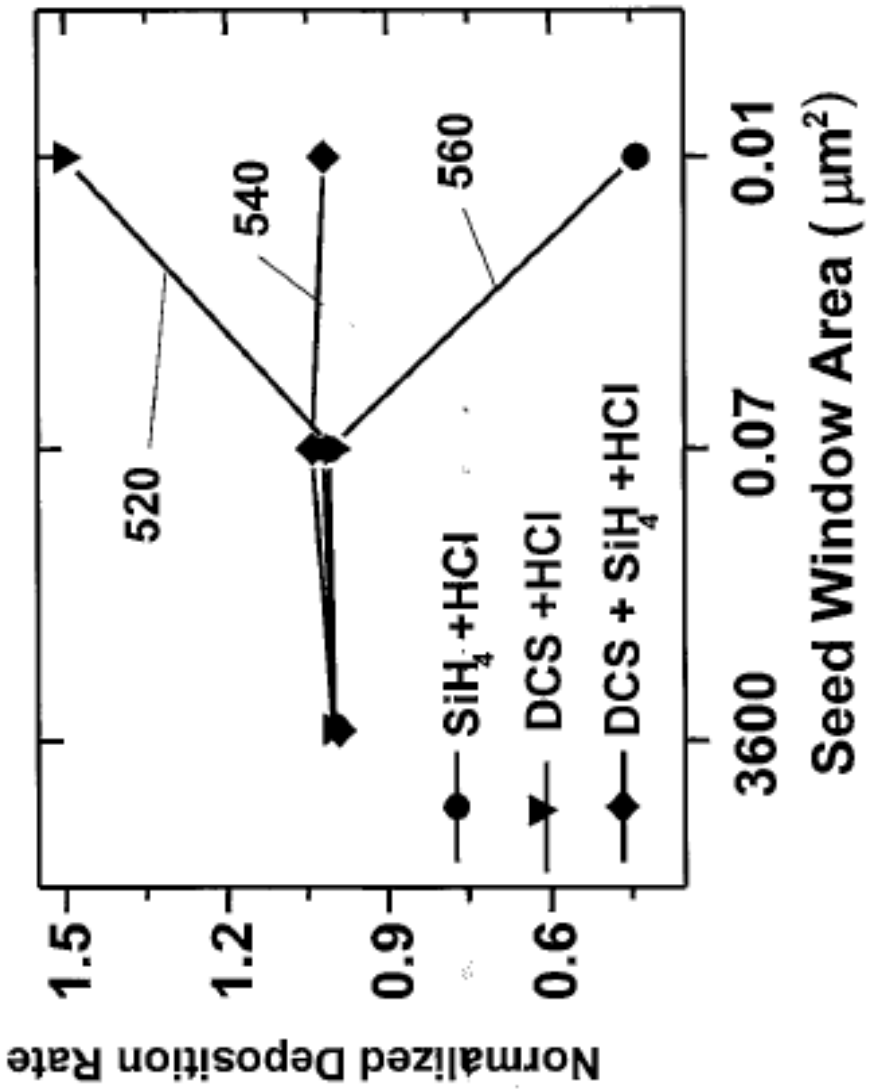
Normalized Deposition Rate
1.5
1.2
0.9
0.6
3600
0.07
0.01
Seed Window Area (μm²)
520
540
560
SiH4 +HCl
DCS +HCl
DCS + SiH4 +HCl

Fig. 5